



# Updates on MOS Model 20, level 2002

**A. Tajic and A.C.T. Aarts\***

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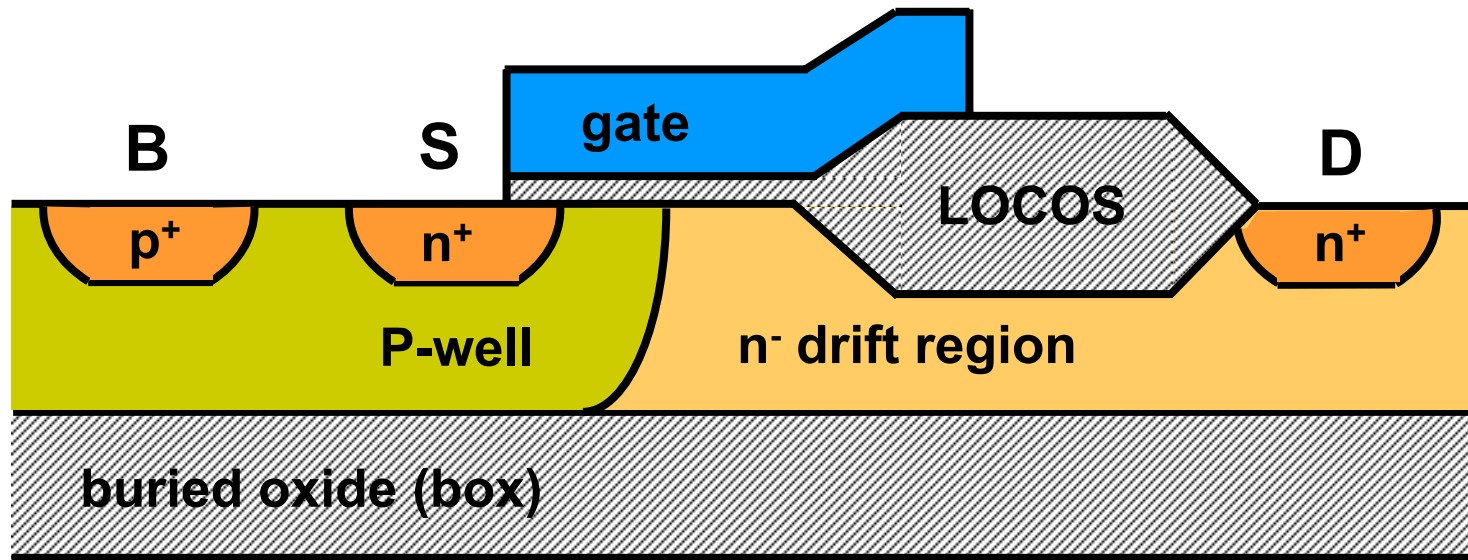
**CMC, Oct 11<sup>th</sup>, 2006**



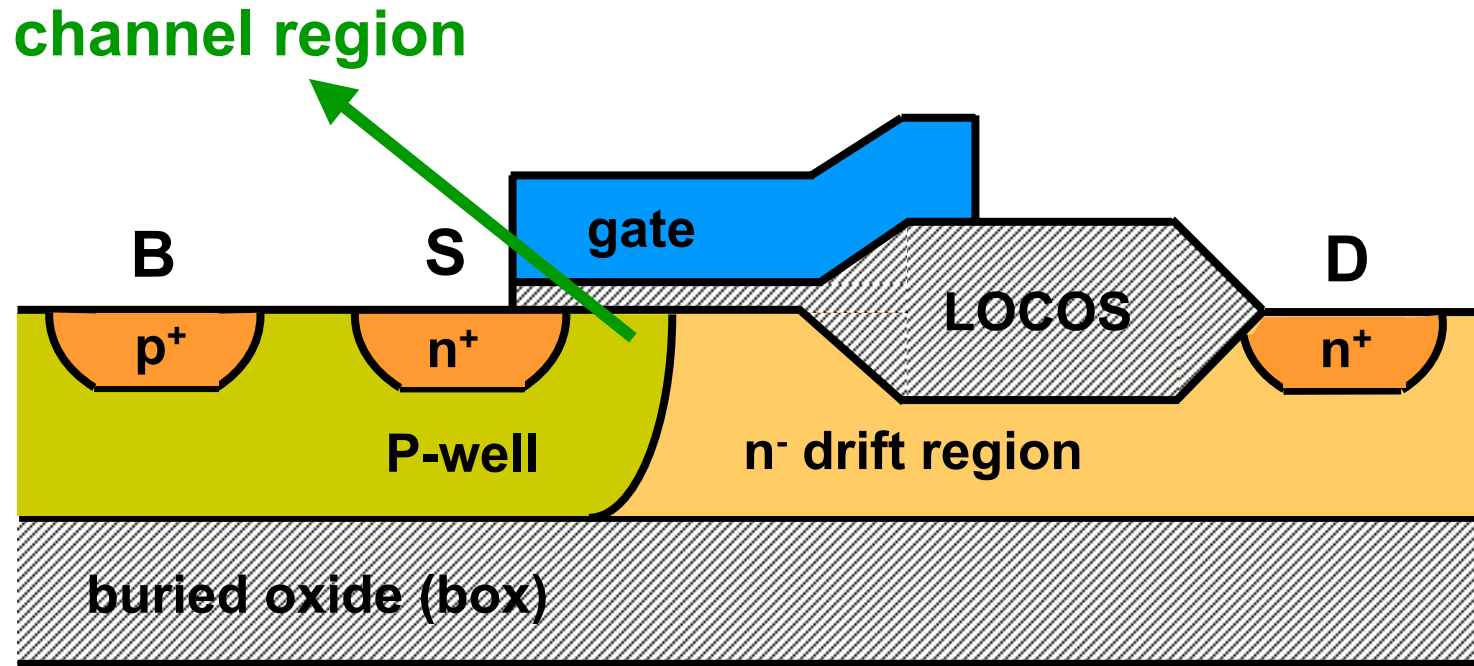
# contents

- ▶ **introduction**
- ▶ **new avalanche current modelling**
- ▶ **update of C-code in SimKit**
- ▶ **update of model documentation**
- ▶ **future plans**

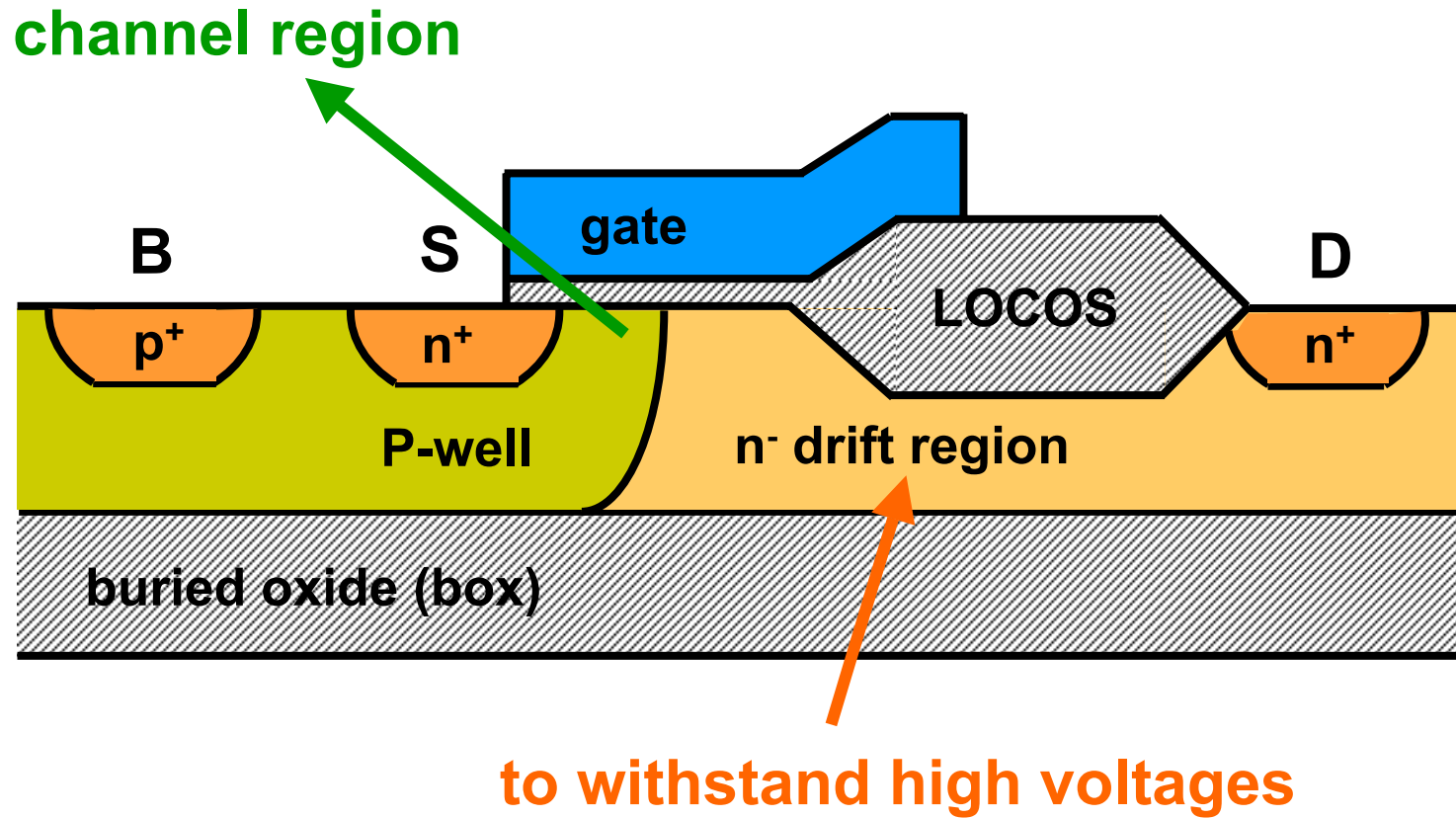
# introduction: (SOI-)LDMOS devices



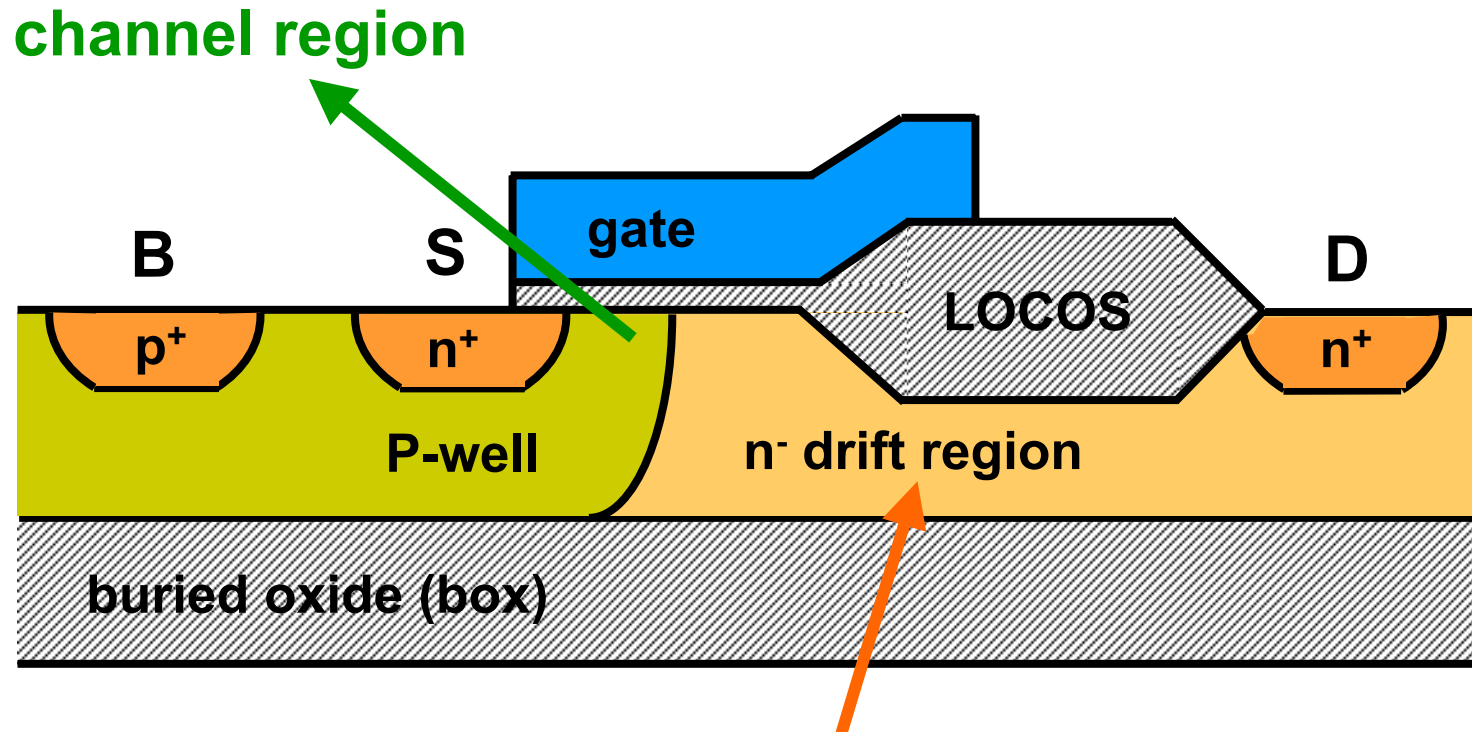
# introduction: (SOI-)LDMOS devices



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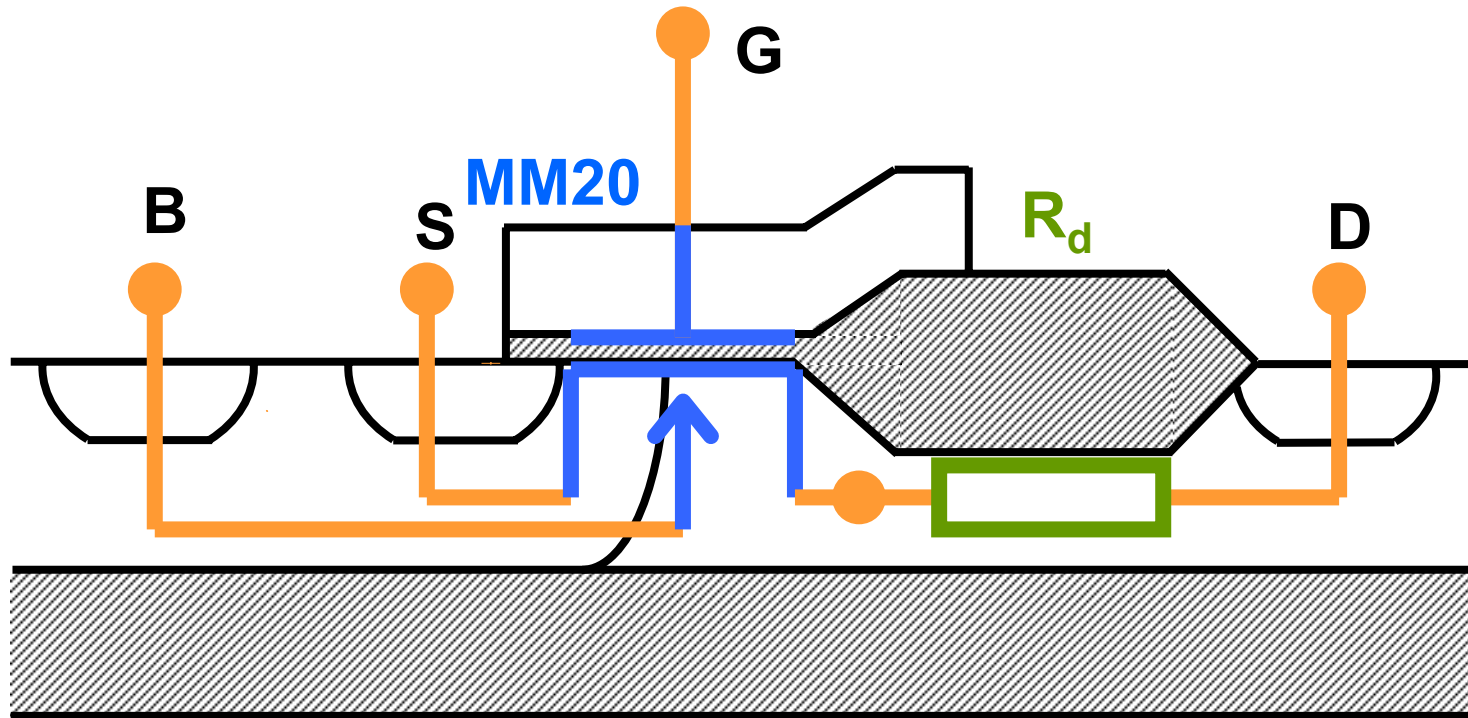
## introduction: (SOI-)LDMOS devices



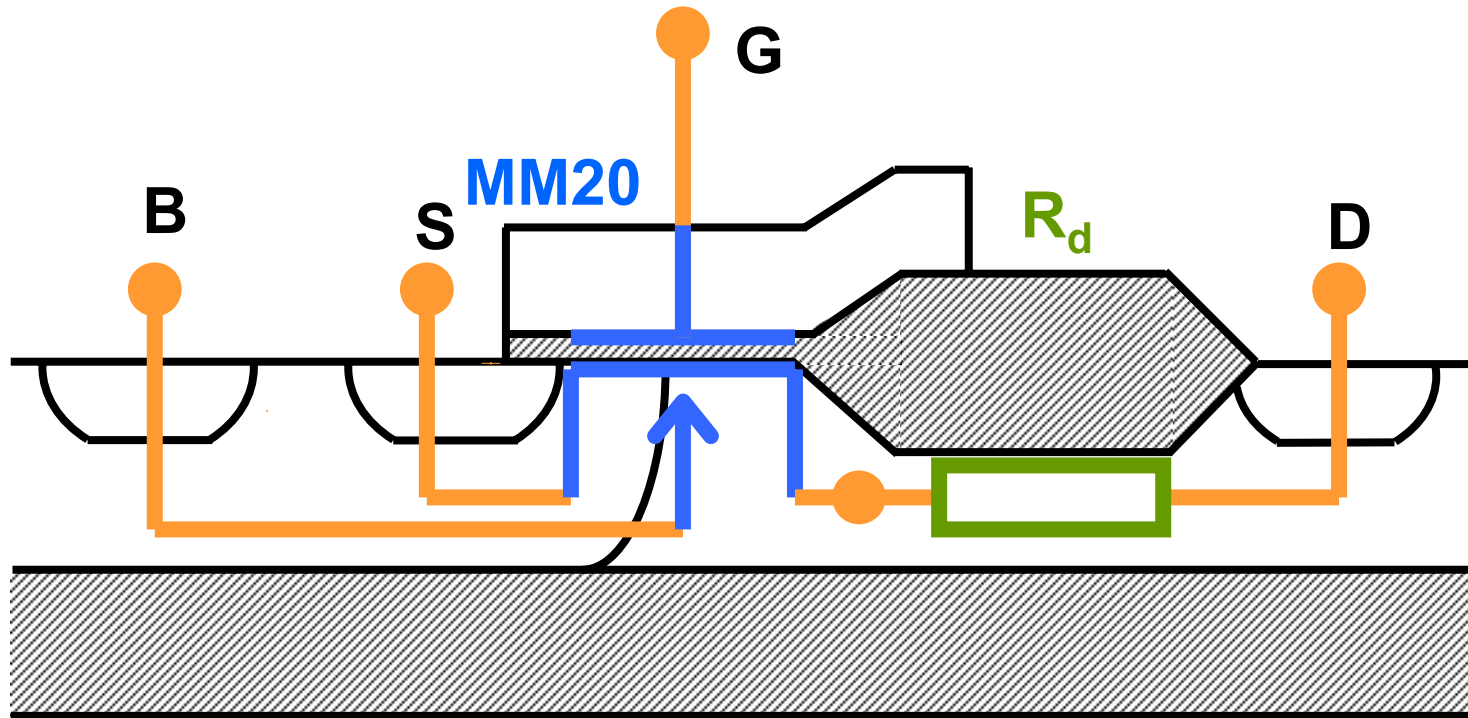
to withstand high voltages  
drain voltages vary between  
12 V and 1200 V



# introduction: (SOI-)LDMOS modelling

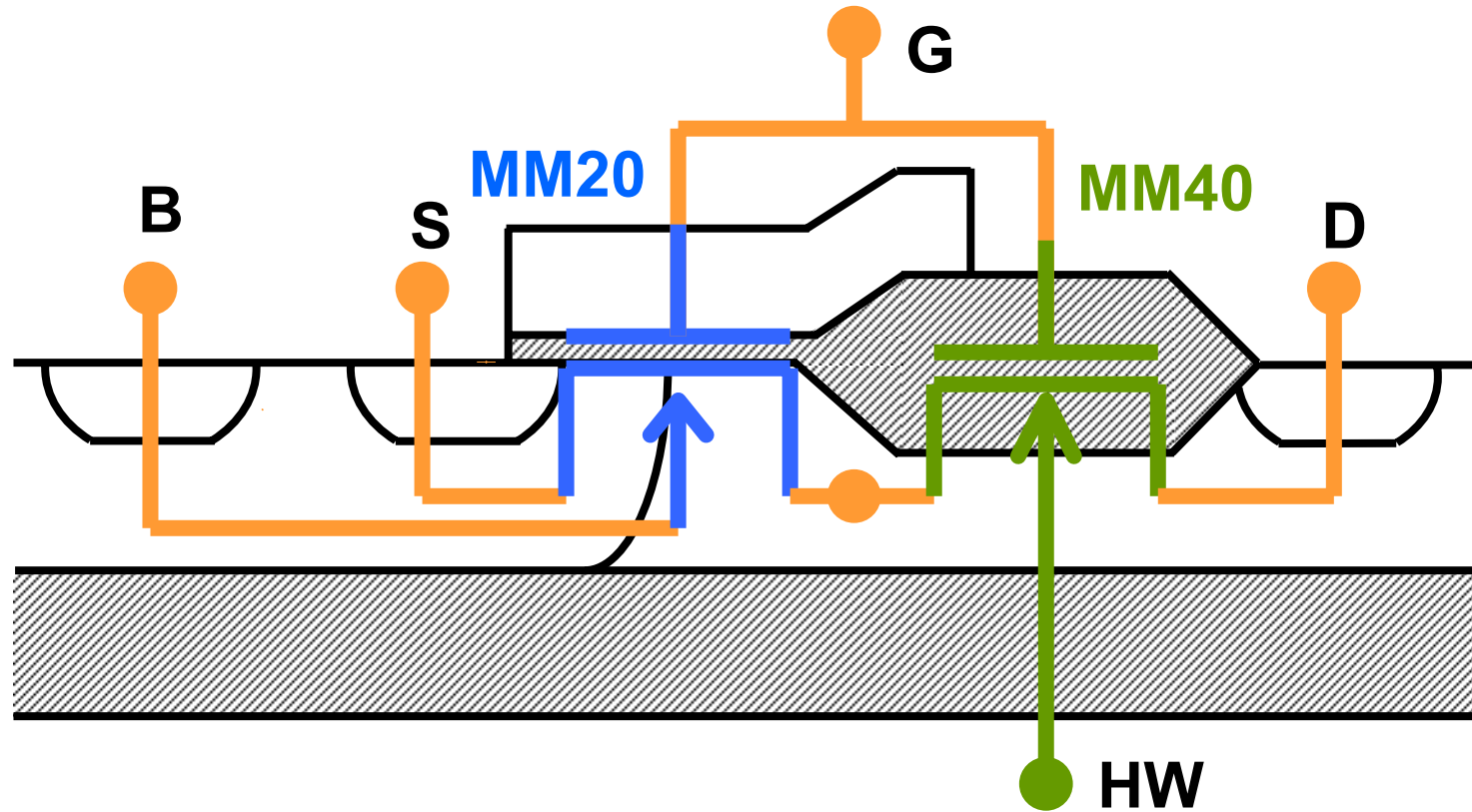


# introduction: (SOI-)LDMOS modelling

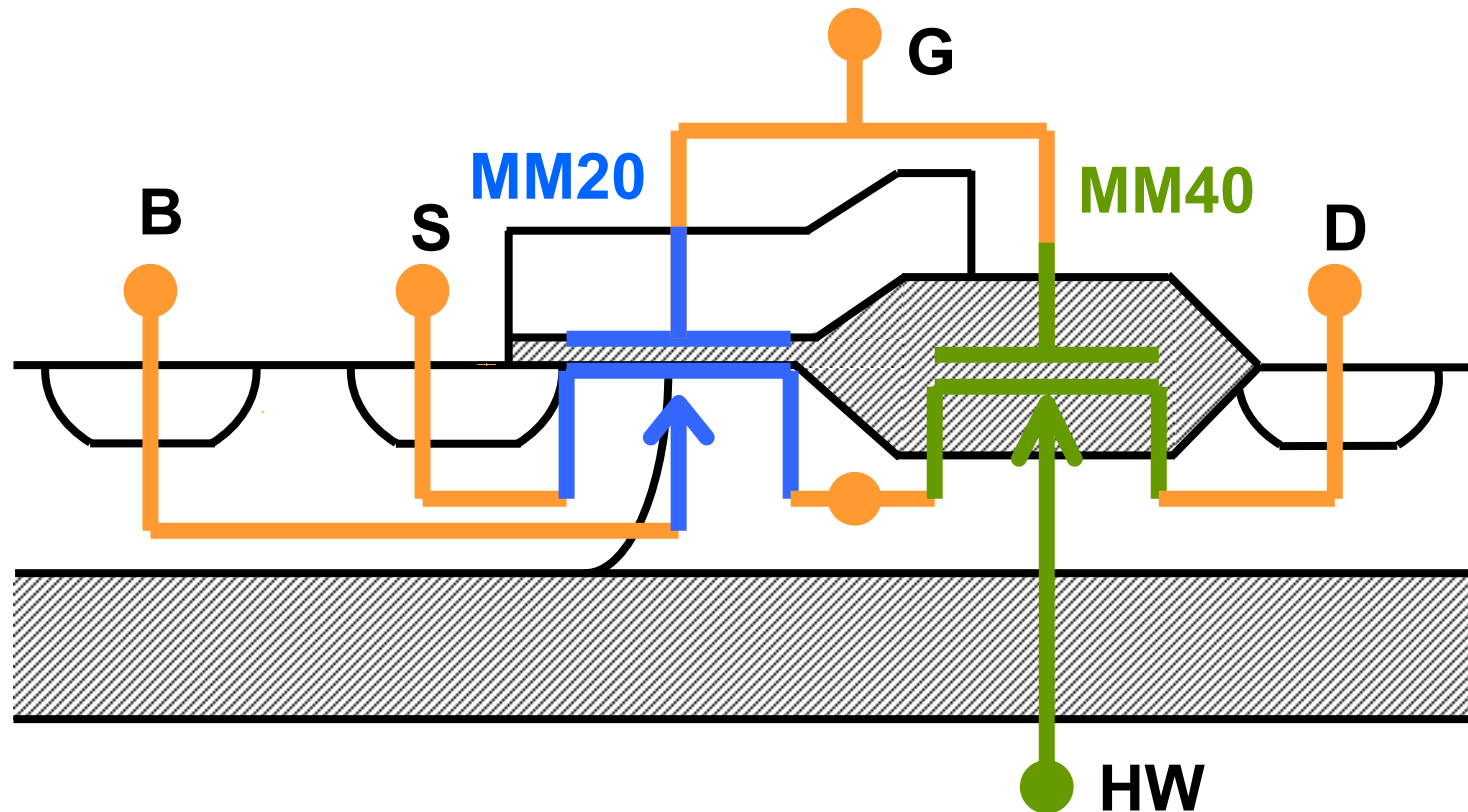


**MOS Model 20 describes electrical behaviour of region under thin gate oxide of a high-voltage MOS device**

# introduction: (SOI-)LDMOS modelling

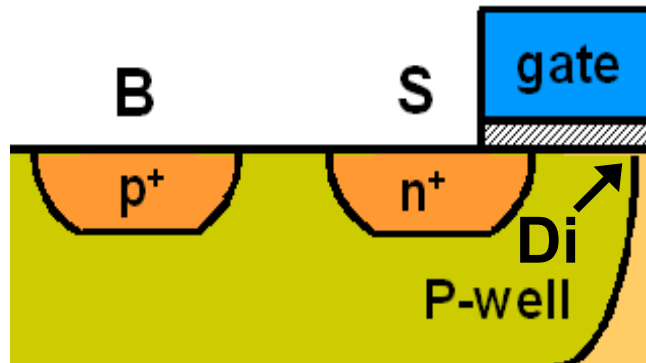


## introduction: (SOI-)LDMOS modelling



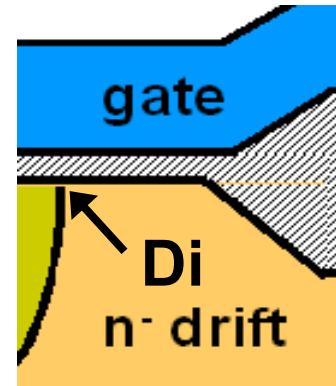
**MOS Model 40 describes electrical behaviour of region under thick gate oxide of a high-voltage MOS device**

## introduction: MOS Model 20, level 2002



### channel region:

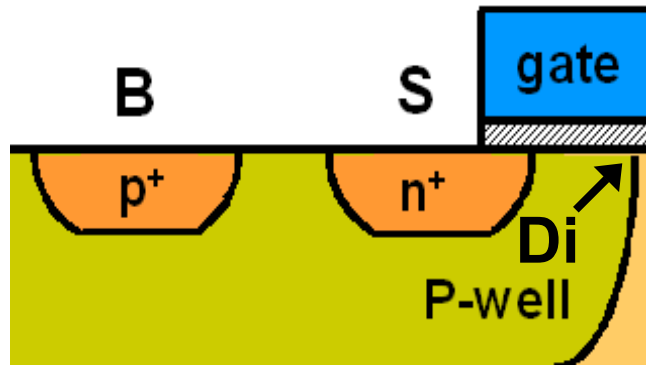
- surface-potential-based
- mobility reduction due to vertical electric field
- velocity saturation
- channel length modulation
- DIBL & static feedback
- avalanche



### drift region:

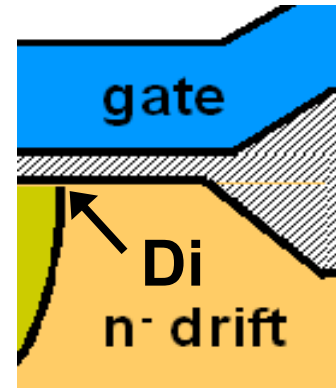
- accumulation
- depletion
- bulk current
- mobility reduction due to vertical electric field
- velocity saturation

## introduction: MOS Model 20, level 2002



### channel region:

- surface-potential-based
- mobility reduction due to



### drift region:

- accumulation
- depletion

### for more information:

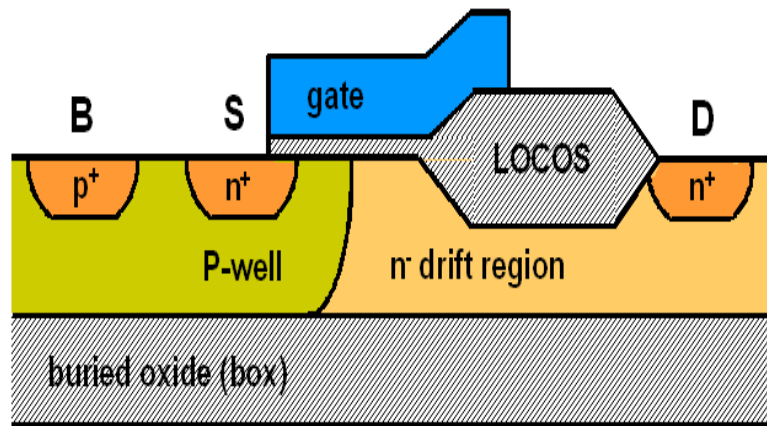
[http://www.eigroup.org/cmc/minutes/2q06\\_presentations/cmc\\_mm20\\_www.pdf](http://www.eigroup.org/cmc/minutes/2q06_presentations/cmc_mm20_www.pdf)

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- ▶ **new avalanche current modelling**
- ▶ update of C-code in SimKit
- ▶ update of model documentation
- ▶ future plans

# avalanche multiplication current (history of problem)

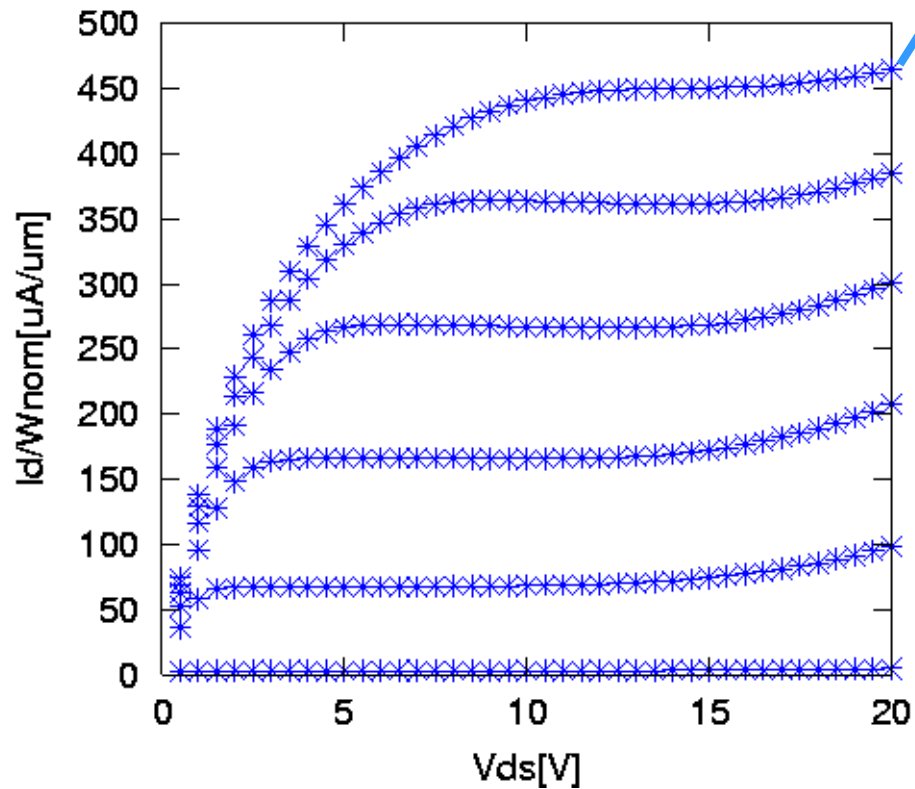
## I-V characteristics



# avalanche multiplication current (history of problem)

I-V characteristics  
 $V_{gs}=1/.../6$  V

measured

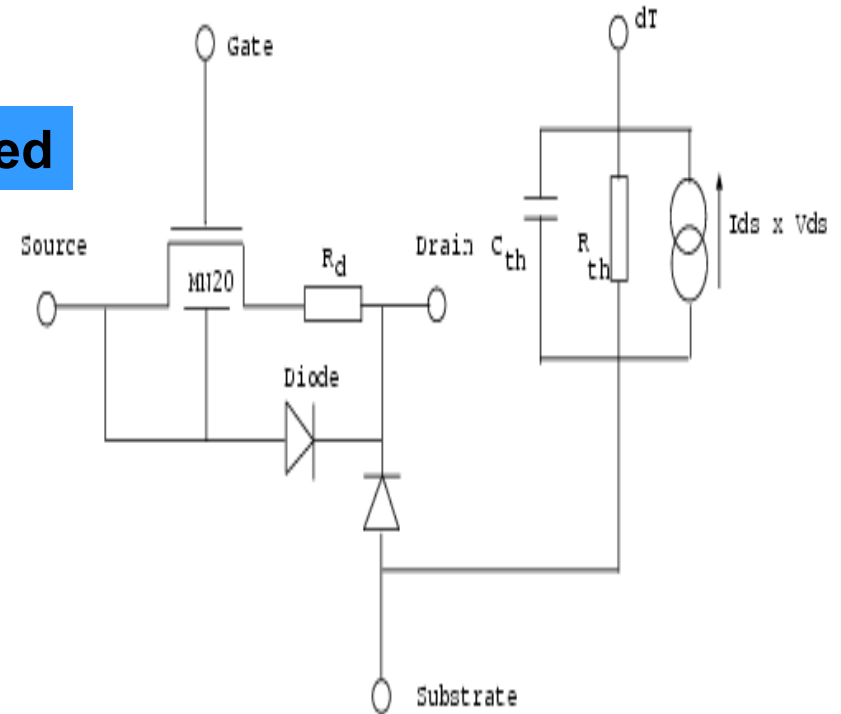
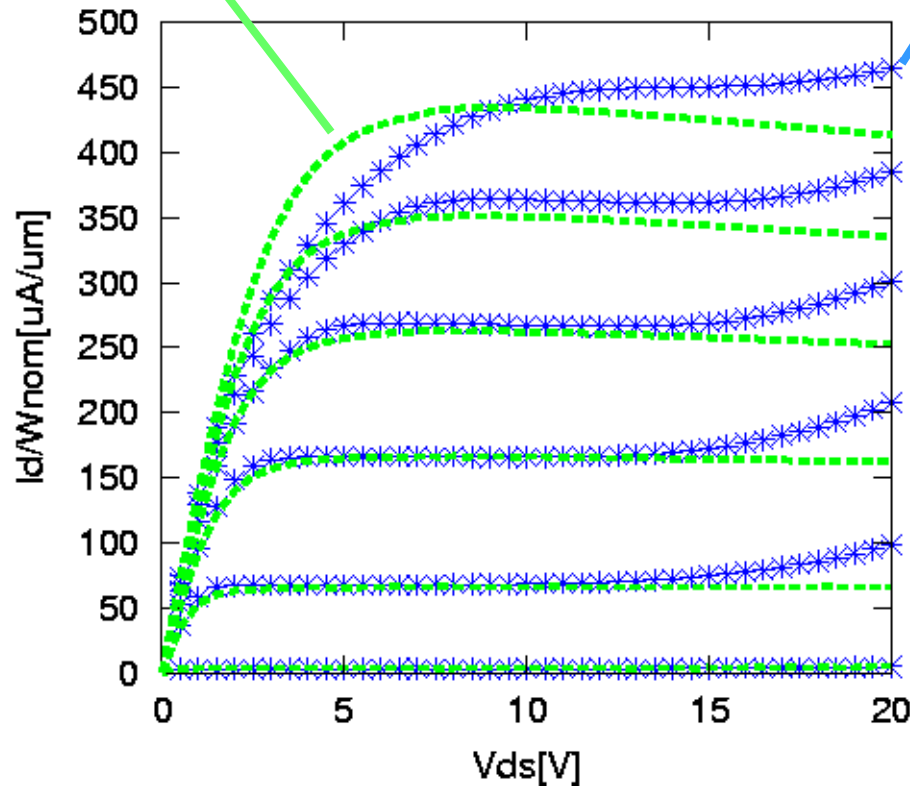


# avalanche multiplication current (history of problem)

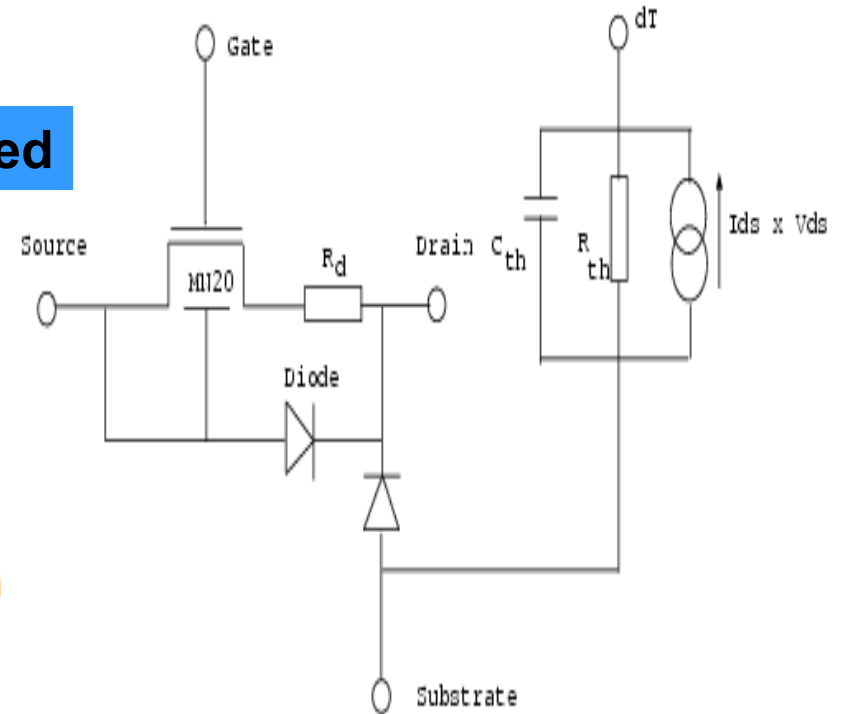
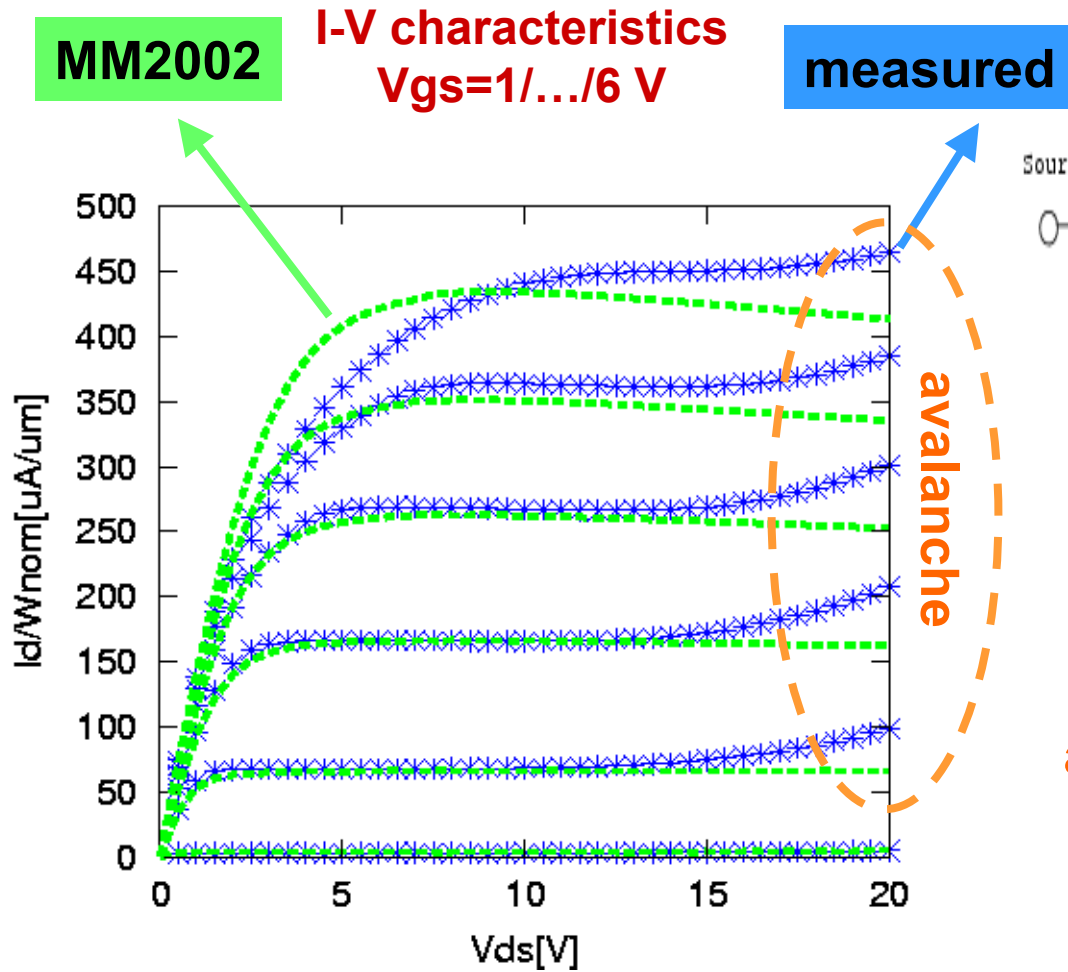
**MM2002**

**I-V characteristics  
 $V_{gs}=1/.../6$  V**

**measured**

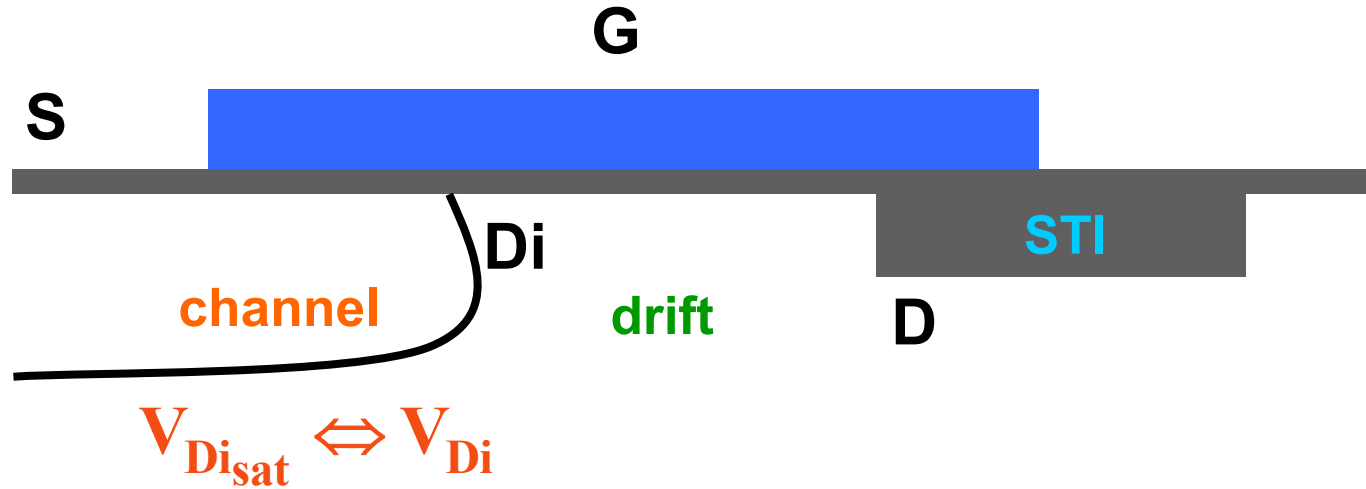


# avalanche multiplication current (history of problem)

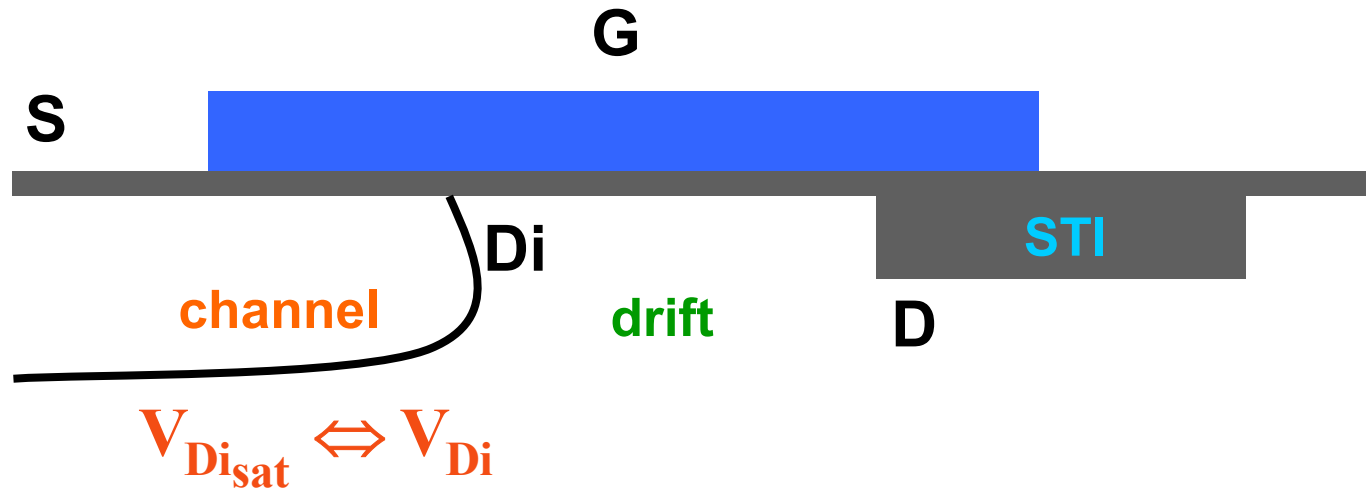


**avalanche current modelling  
is poor in  
MOS Model 2002**

# avalanche current formulation



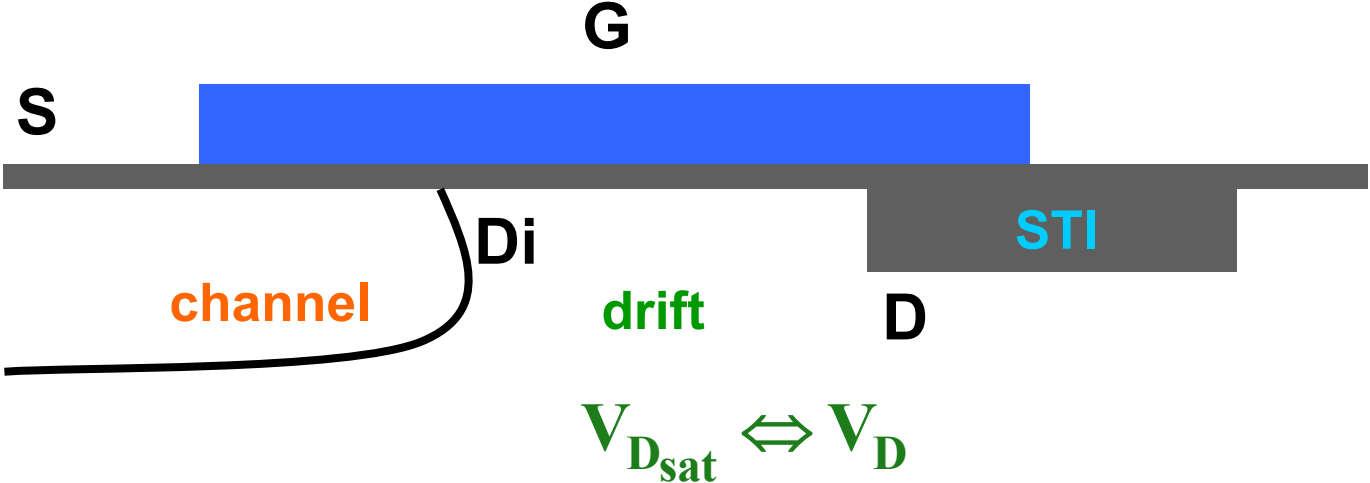
# avalanche current formulation



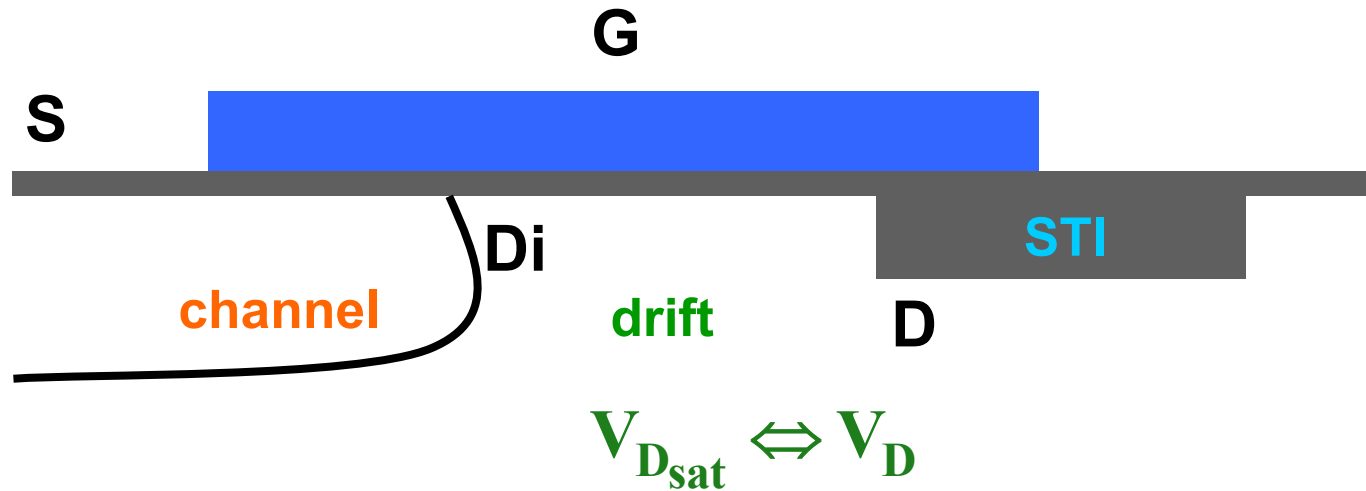
$$I_{avlCH} = a_{1CH} |I_{DS}| \exp \left[ -\frac{a_{2CH}}{|V_{Di}| - a_{3CH} V_{Di,sat}} \right]$$

channel region contribution

# avalanche current formulation



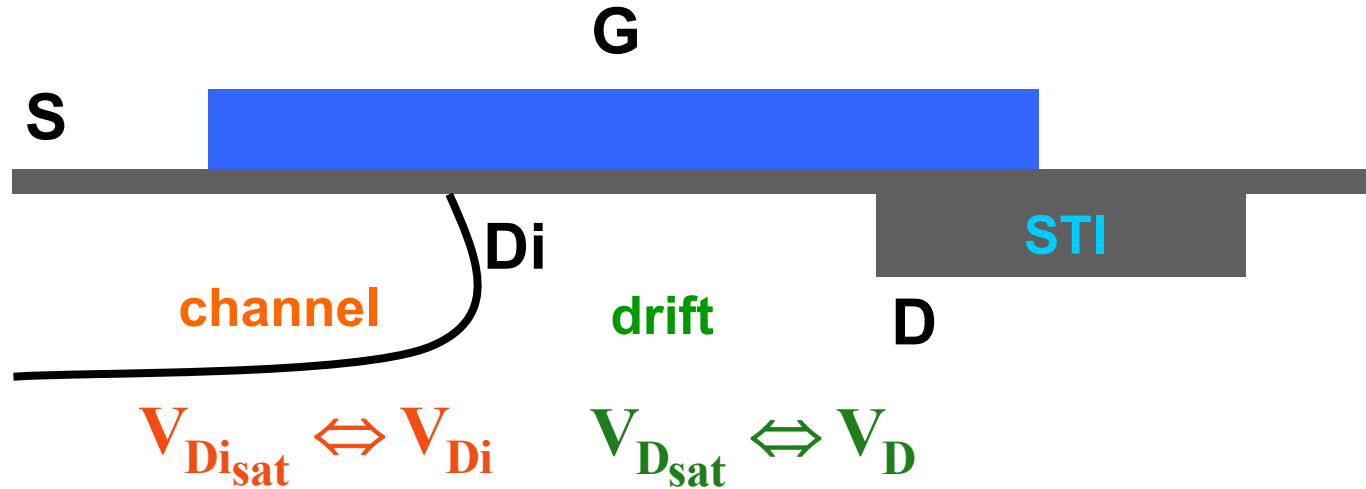
# avalanche current formulation



$$I_{avl_{DR}} = a_{1DR} |I_{DS}| \exp \left[ -\frac{a_{2DR}}{|V_D| - a_{3DR} V_{D_{sat}}} \right]$$

drift region contribution

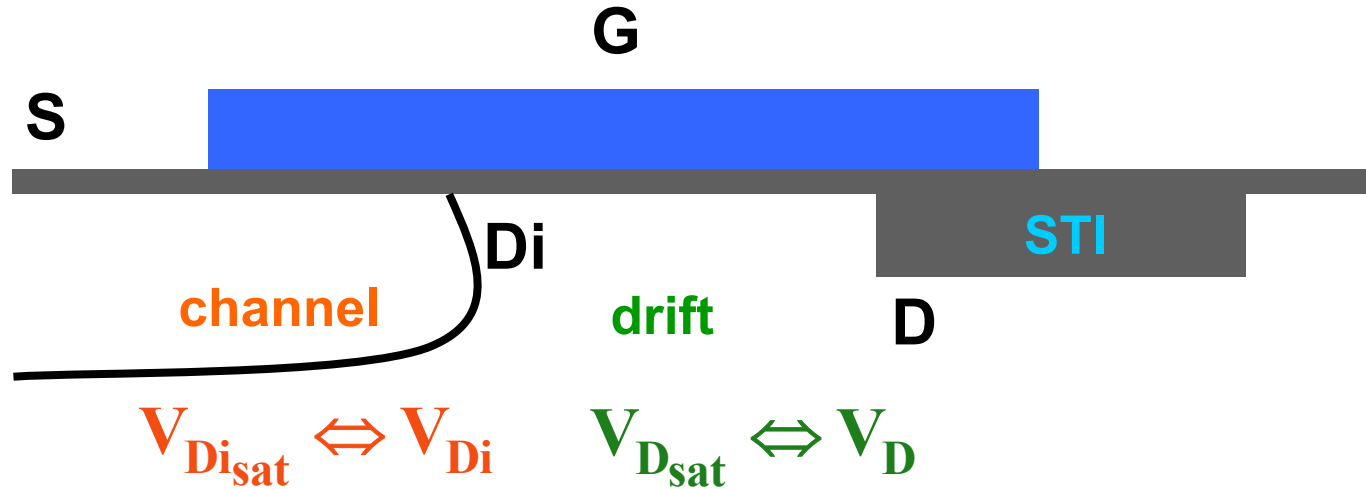
# avalanche current formulation



$$I_{\text{avl}} = I_{\text{avlCH}}$$

old avalanche model

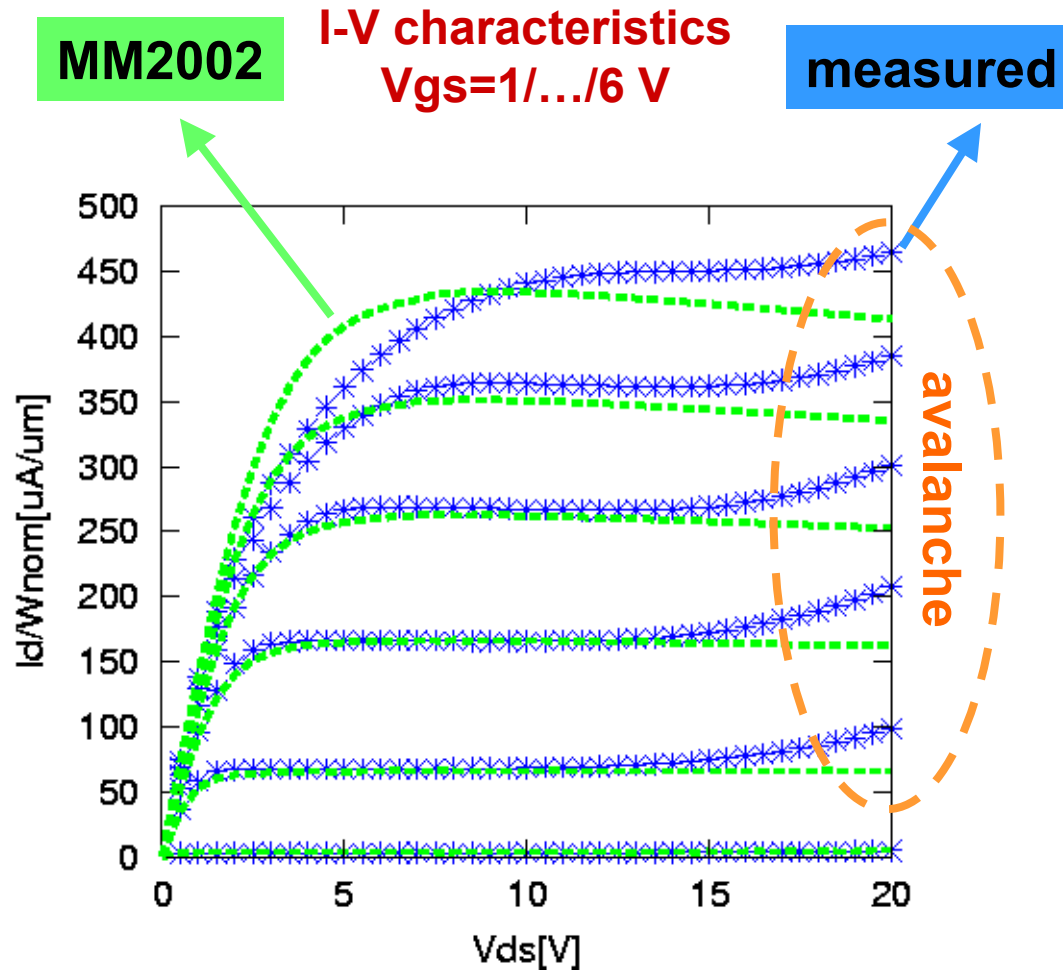
# avalanche current formulation



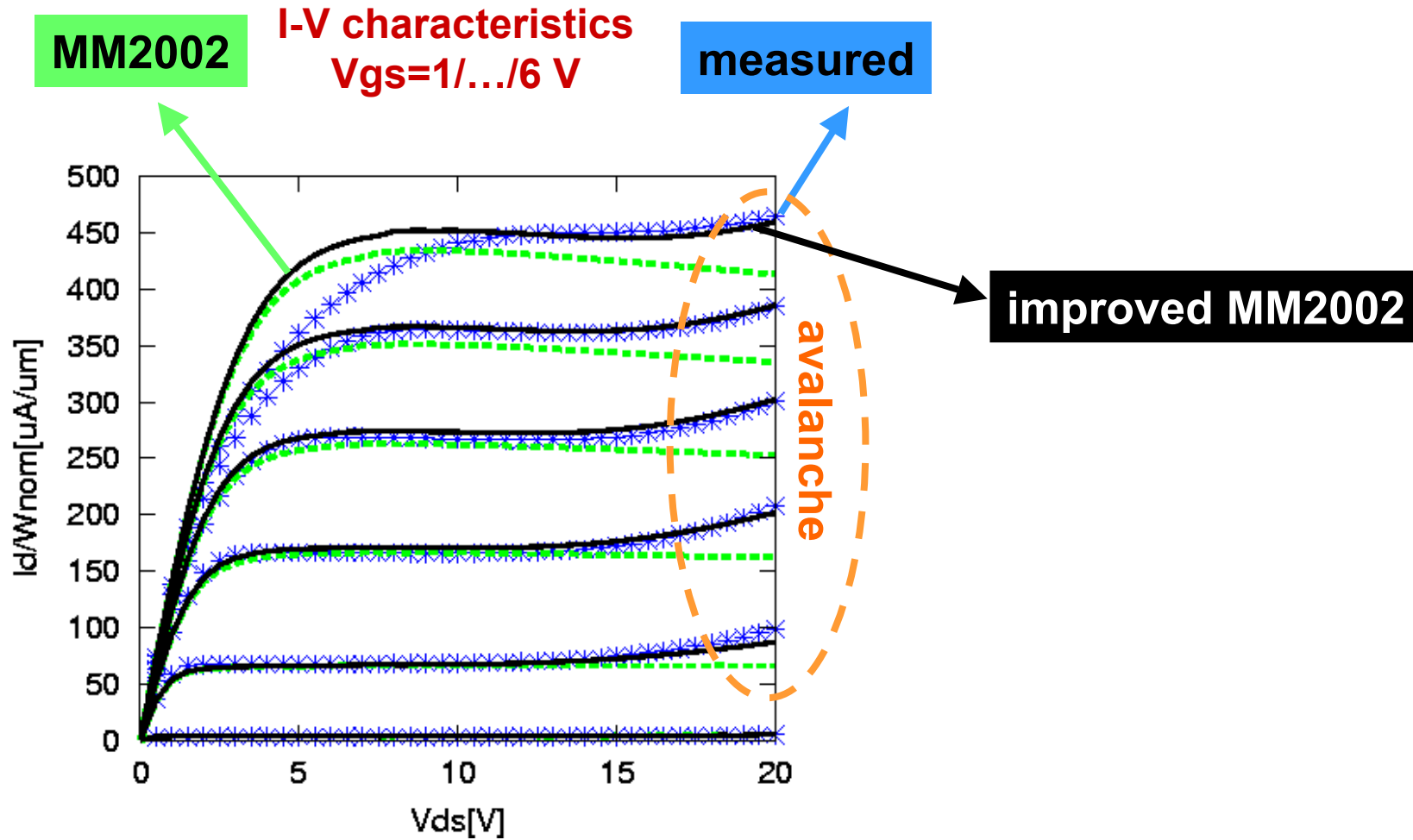
$$I_{avl} = I_{avlCH} + I_{avlDR}$$

new avalanche model

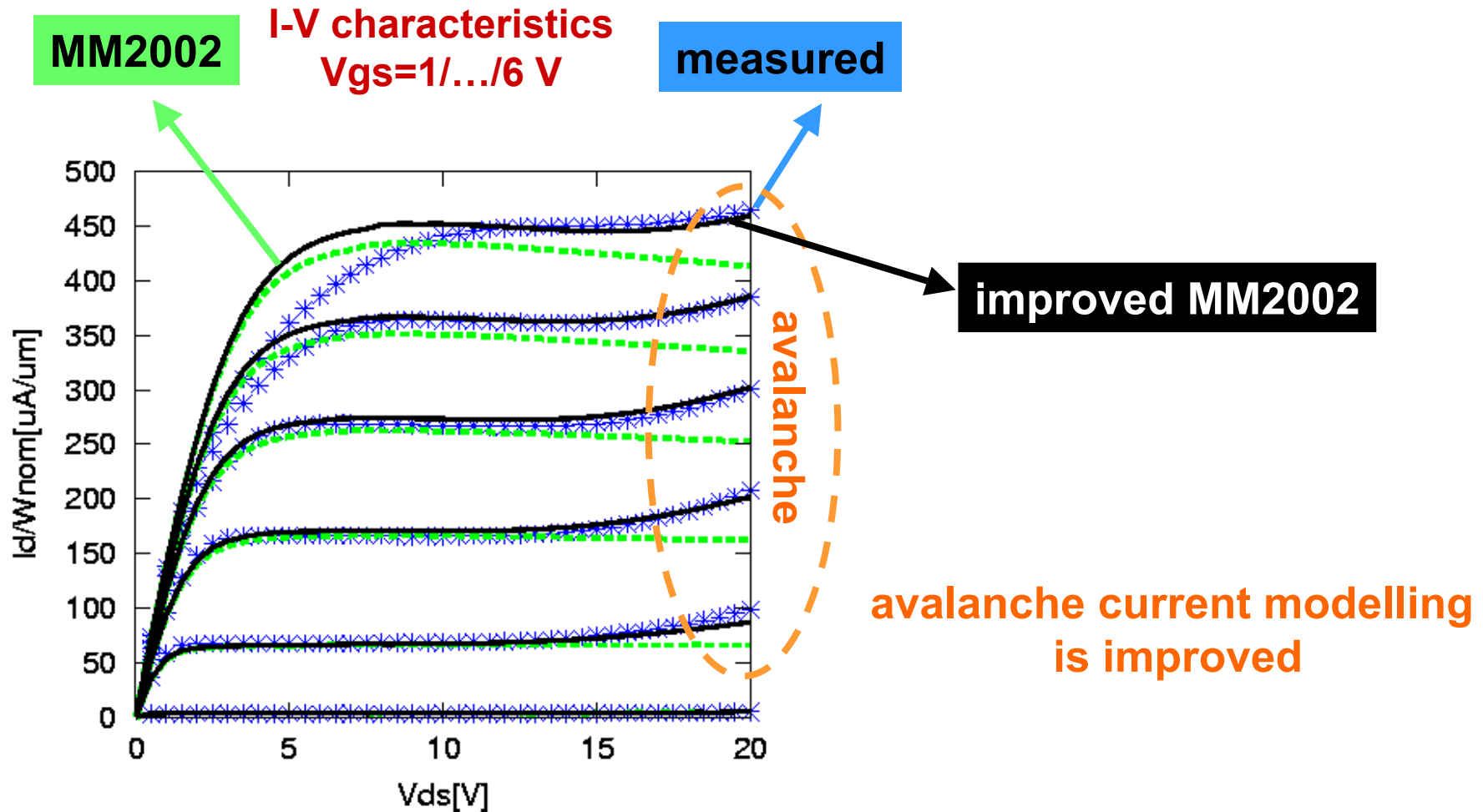
# avalanche multiplication current



# avalanche multiplication current (comparing old & new models)



# avalanche multiplication current (comparing old & new models)



# MOS Model 20, level 2002

update of avalanche model

## electrical parameters:

### - channel region parameters

- **A1CH:** Factor of channel avalanche current at reference temperature
- **STA1CH:** Temperature scaling coefficient for A1CH
- **A2CH:** Exponent of weak avalanche current related to channel region
- **A3CH:** Factor of internal drain-source voltage above which avalanche occurs

### - drift region parameters

- **A1DR:** Factor of drift avalanche current at reference temperature
- **STA1DR:** Temperature scaling coefficient for A1DR
- **A2DR:** Exponent of weak avalanche current related to drift region
- **A3DR:** Factor of drain-source voltage above which avalanche occurs

# MOS Model 20, level 2002

update of avalanche model

## geometrical parameters:

### - channel region parameters

- **A1CHR:** Factor of channel avalanche current of an infinitely wide transistor, at reference temperature
- **SWA1CH:** Width scaling coefficient for A1CH
- **STA1CH:** Temperature scaling coefficient for A1CH
- **A2CH:** Exponent of weak avalanche current related to channel region
- **A3CH:** Factor of internal drain-source voltage above which avalanche occurs

# MOS Model 20, level 2002

update of avalanche model

## geometrical parameters:

### - drift region parameters

- **A1DRR:** Factor of drift avalanche current of an infinitely wide transistor, at reference temperature
- **SWA1DR:** Width scaling coefficient for A1DR
- **STA1DR:** Temperature scaling coefficient for A1DR
- **A2DR:** Exponent of weak avalanche current related to drift region
- **A3DR:** Factor of drain-source voltage above which avalanche occurs

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## update of C-code in SimKit

MOS Model 20: 2002.1, to be released in Simkit 2.4 (October 2006), will include:

- new avalanche current model
- corrections based on the comments of Geoffrey Coram (Analog Devices):
  - correct clip-low value for  $W$  and  $WD$ , to be set at 1nm
  - in the iterative procedure of calculating the internal drain, one gets

$$I_{ch}=0 \text{ for } V_{dis}=0$$

$$I_{dr}=0 \text{ for } V_{dis}=V_{ds}$$

thus no need to calculate  $I_{ch}$  and  $I_{dr}$

... and fixes to various smaller issues/inconsistencies  
(having no impact on characterization)

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## update of model documentation

**MM2002 model documentation, expected to be released in October 2006, will include:**

- **new avalanche current model**
- **corrections based on the comments of Geoffrey Coram (AD) and Ron Vennix (ED&T):**
  - **correct clip-low value for W and WD, to be set at 1nm**
  - **correcting some formulas in the iterative procedure**
  - **correct formula for the drift charge**

**... and some smaller issues**

## update of model documentation

**MM2002 model documentation, expected to be released in October 2006, will include:**

- **new avalanche current model**
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  - **correct clip-low value for W and WD, to be set at 1nm**
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  - **correct formula for the drift charge**

**... and some smaller issues**

**documentation and source code available on website:  
[http://www.nxp.com/Philips\\_Models/high\\_voltage/model20/index.html](http://www.nxp.com/Philips_Models/high_voltage/model20/index.html)**



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## future plans

- self-heating in MOS Model 2002 planned for SimKit 2.5, to be released in March 2007
- improving quasi-saturation behaviour

